

Abstract

Method for producing an antireflection coating

A method for producing an antireflection coating on a substrate (10) is specified, comprising the method steps:

- generating a first nanostructure (11) in a first material by means of a first plasma etching process, wherein the first material is the material of the substrate (10) or the material of a layer (1) made of a first organic material applied onto the substrate (10),
- applying a layer (2) made of a second material onto the first nanostructure (11), wherein the second material is an organic material, and
- generating a second nanostructure (12) in the layer (2) made of the second material by means of a second plasma etching process, wherein the second material has a higher etching rate than the first material when carrying out the second plasma etching process.

Significant figure: Fig. 4F